

Customer No.: 31561
Docket No.: 11439-US-PA
Application No.: 10/605,160

In the Specification:

Please amend [0016] as follows:

[0016] Fig. 1 is a diagram showing the component layout of an ionized physical vapor deposition apparatus according to one preferred embodiment of this invention. The ionized physical vapor deposition (I-PVD) apparatus comprises a reaction chamber 100, a wafer pedestal 104, a target 106, an ionization unit [[106]] 108 and a conductive mesh 110.